## ADVANCED MASK

## TECHNOLOGY CENTER

# EWMA control charts for monitoring normal variance 

Sven Knoth

Fifth Annual Meeting of ENBIS
Newcastle, September 2005

## ADVANCED MASK

## Outline

1. Variance monitoring,
2. EWMA,
3. Numerical challenges,
4. Application,
5. Conclusions.

## ADVANCED MASK

## TECHNOLOGY CENTER

## Statistics \& Monitoring

| Statistical Process Control (SPC) | industrial statistics |
| :--- | :--- |
| Change Point Detection Schemes | mathematical statistics |
| Surveillance | biostatistics |
| Structural Breaks | econometrics |

## ADVANCED MASK

## TECHNOLOGY CENTER

Objective of "Control Charting"

Woodall/Montgomery (1999)
... in the area of control charting and SPC. As a general definition, we include in this area any statistical method designed to detect changes in a process over time.

## ADVANCED MASK

## TECHNOLOGY CENTER

Change Point Model (for the mean)

- $\left\{X_{i j}\right\}$ - series of random variables with $\operatorname{cdf}\left\{P_{i}\right\}$, $j=1,2, \ldots, n, n-$ subgroup size,


## ADVANCED MASK

## TECHNOLOGY CENTER

Change Point Model (for the mean)

- $\left\{X_{i j}\right\}$ - series of random variables with $\operatorname{cdf}\left\{P_{i}\right\}$, $j=1,2, \ldots, n, n-$ subgroup size,
- assumptions: $P_{i}(x)=\Phi\left(\left(x-\mu_{(i)}\right) / \sigma_{(i)}\right)$, independence,


## ADVANCED MASK

## Change Point Model (for the mean)

- $\left\{X_{i j}\right\}$ - series of random variables with $\operatorname{cdf}\left\{P_{i}\right\}$, $j=1,2, \ldots, n, n-$ subgroup size,
- assumptions: $P_{i}(x)=\Phi\left(\left(x-\mu_{(i)}\right) / \sigma_{(i)}\right)$, independence,
- model:

$$
\mu_{(i)}=\left\{\begin{array}{ll}
\mu_{0} & , i<m \\
\mu_{1} & , i \geq m
\end{array}, \sigma_{(i)}=\sigma_{0}\right.
$$

with unkown parameter $m$ (change point),

## ADVANCED MASK

## Change Point Model (for the mean)

- $\left\{X_{i j}\right\}$ - series of random variables with $\operatorname{cdf}\left\{P_{i}\right\}$, $j=1,2, \ldots, n, n-$ subgroup size,
- assumptions: $P_{i}(x)=\Phi\left(\left(x-\mu_{(i)}\right) / \sigma_{(i)}\right)$, independence,
- model:

$$
\mu_{(i)}=\left\{\begin{array}{ll}
\mu_{0} & , i<m \\
\mu_{1} & , i \geq m
\end{array}, \sigma_{(i)}=\sigma_{0}\right.
$$

with unkown parameter $m$ (change point),

- more formal objective of SPC:
detect $m$ as fast and reliable as possible.


## ADVANCED MASK

## TECHNOLOGY CENTER

## Variance monitoring

- variance within samples (e.g., uniformity measures),


## ADVANCED MASK

## TECHNOLOGY CENTER

## Variance monitoring

- variance within samples (e.g., uniformity measures),
- sample statistics such as $S^{2}, S, R$ or certain robust estimators, e. g.

$$
S_{i}^{2}=\frac{1}{n-1} \sum_{j=1}^{n}\left(X_{i j}-\bar{X}_{i}\right)^{2}
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

## Variance monitoring

- variance within samples (e.g., uniformity measures),
- sample statistics such as $S^{2}, S, R$ or certain robust estimators, e. g.

$$
S_{i}^{2}=\frac{1}{n-1} \sum_{j=1}^{n}\left(X_{i j}-\bar{X}_{i}\right)^{2}
$$

- change point model:

$$
\sigma_{(i)}^{2}= \begin{cases}\sigma_{0}^{2} & , i<m \\ \sigma_{1}^{2} & , i \geq m\end{cases}
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

## Variance monitoring

- variance within samples (e.g., uniformity measures),
- sample statistics such as $S^{2}, S, R$ or certain robust estimators, e. g.

$$
S_{i}^{2}=\frac{1}{n-1} \sum_{j=1}^{n}\left(X_{i j}-\bar{X}_{i}\right)^{2}
$$

- change point model:

$$
\sigma_{(i)}^{2}= \begin{cases}\sigma_{0}^{2} & , i<m \\ \sigma_{1}^{2} & , i \geq m\end{cases}
$$

- single variance change or simultaneous mean/variance change.


## ADVANCED MASK

## TECHNOLOGY CENTER

Upper $S^{2}$ EWMA control charts
Exponentially Weighted Moving Average
Roberts (1959), Wortham/Ringer (1971), Sweet (1986)

## ADVANCED MASK

## TECHNOLOGY CENTER

## Upper $S^{2}$ EWMA control charts

Exponentially Weighted Moving Average
Roberts (1959), Wortham/Ringer (1971), Sweet (1986)

$$
Z_{0}=z_{0}=E_{\sigma_{0}}\left(S_{i}^{2}\right)=\sigma_{0}^{2}
$$

## ADVANCED MASK

Upper $S^{2}$ EWMA control charts
Exponentially Weighted Moving Average
Roberts (1959), Wortham/Ringer (1971), Sweet (1986)

$$
\begin{aligned}
& Z_{0}=z_{0}=E_{\sigma_{0}}\left(S_{i}^{2}\right)=\sigma_{0}^{2} \\
& Z_{i}=(1-\lambda) Z_{i-1}+\lambda S_{i}^{2} \quad, \lambda \in(0,1]
\end{aligned}
$$

## ADVANCED MASK

Upper $S^{2}$ EWMA control charts
Exponentially Weighted Moving Average Roberts (1959), Wortham/Ringer (1971), Sweet (1986)

$$
\begin{aligned}
& Z_{0}=z_{0}=E_{\sigma_{0}}\left(S_{i}^{2}\right)=\sigma_{0}^{2} \\
& Z_{i}=(1-\lambda) Z_{i-1}+\lambda S_{i}^{2} \quad, \lambda \in(0,1]
\end{aligned}
$$

$$
E_{\sigma_{0}}\left(Z_{i}\right)=\sigma_{0}^{2}
$$

$$
\operatorname{Var}_{\sigma_{0}}\left(Z_{i}\right)=\frac{\lambda}{2-\lambda}\left(1-(1-\lambda)^{2 i}\right) \times \operatorname{Var}_{\sigma_{0}}\left(S_{i}^{2}\right)
$$

$$
\rightarrow \frac{\lambda}{2-\lambda} \times \frac{2}{n-1} \sigma_{0}^{4}=: \sigma_{Z}^{2}
$$

## ADVANCED MASK

Upper $S^{2}$ EWMA control charts
Exponentially Weighted Moving Average Roberts (1959), Wortham/Ringer (1971), Sweet (1986)

$$
\begin{aligned}
& Z_{0}=z_{0}=E_{\sigma_{0}}\left(S_{i}^{2}\right)=\sigma_{0}^{2}, \\
& Z_{i}=(1-\lambda) Z_{i-1}+\lambda S_{i}^{2} \quad, \lambda \in(0,1],
\end{aligned}
$$

$$
E_{\sigma_{0}}\left(Z_{i}\right)=\sigma_{0}^{2}
$$

$$
\operatorname{Var}_{\sigma_{0}}\left(Z_{i}\right)=\frac{\lambda}{2-\lambda}\left(1-(1-\lambda)^{2 i}\right) \times \operatorname{Var}_{\sigma_{0}}\left(S_{i}^{2}\right)
$$

$$
\rightarrow \frac{\lambda}{2-\lambda} \times \frac{2}{n-1} \sigma_{0}^{4}=: \sigma_{Z}^{2},
$$

$$
L=\inf \left\{i \in \mathbb{N}: Z_{i}>\sigma_{0}^{2}+c \sigma_{Z}\right\} .
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

Modifications

$$
Z_{i}^{*}=\max \left\{(1-\lambda) Z_{i-1}^{*}+\lambda S_{i}^{2}, \sigma_{0}^{2}\right\},
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

## Modifications

$$
\begin{aligned}
Z_{i}^{*} & =\max \left\{(1-\lambda) Z_{i-1}^{*}+\lambda S_{i}^{2}, \sigma_{0}^{2}\right\}, \\
L_{\text {two-sided }} & =\inf \left\{i \in \mathbb{N}: Z_{i}-\sigma_{0}^{2} \notin\left[c_{\text {ower }}, c_{\text {upper }}\right] \times \sigma_{Z}\right\},
\end{aligned}
$$

## ADVANCED MASK

## Modifications

$$
\begin{aligned}
Z_{i}^{*} & =\max \left\{(1-\lambda) Z_{i-1}^{*}+\lambda S_{i}^{2}, \sigma_{0}^{2}\right\} \\
L_{\text {two-sided }} & =\inf \left\{i \in \mathbb{N}: Z_{i}-\sigma_{0}^{2} \notin\left[c_{\text {lower }}, c_{\text {upper }}\right] \times \sigma_{Z}\right\},
\end{aligned}
$$

use $S_{i}$ or $\ln S_{i}^{2}$ or $R_{i}$ or $\ldots$

## ADVANCED MASK

## TECHNOLOGY CENTER

Performance measures for control charting

Denote $E_{m}(\cdot)$ the expectation for a change point at $m$.

1. Average Run Length (ARL): $E_{\infty}(L) \& E_{1}(L) \rightsquigarrow E_{\sigma}(L)$

## ADVANCED MASK

## TECHNOLOGY CENTER

Performance measures for control charting

Denote $E_{m}(\cdot)$ the expectation for a change point at $m$.

1. Average Run Length (ARL): $E_{\infty}(L) \& E_{1}(L) \rightsquigarrow E_{\sigma}(L)$
2. Lorden's worst case: $E_{\infty}(L) \& \sup _{m} \operatorname{ess} \sup E_{m}\left((L-m+1)^{+} \mid \mathcal{F}_{m-1}\right)$

## ADVANCED MASK

## TECHNOLOGY CENTER

Performance measures for control charting

Denote $E_{m}(\cdot)$ the expectation for a change point at $m$.

1. Average Run Length (ARL): $E_{\infty}(L) \& E_{1}(L) \rightsquigarrow E_{\sigma}(L)$
2. Lorden's worst case: $E_{\infty}(L) \& \sup _{m} \operatorname{ess} \sup E_{m}\left((L-m+1)^{+} \mid \mathcal{F}_{m-1}\right)$
3. Roberts' steady state: $E_{\infty}(L) \& \lim _{m \rightarrow \infty} E_{m}(L-m+1 \mid L \geq m-1)$
4. ...

## ADVANCED MASK

## TECHNOLOGY CENTER

ARL computation

1. Markov chain approximation (Brook/Evans, 1972, CUSUM) Lucas/Saccucci (1990),

## ADVANCED MASK

## TECHNOLOGY CENTER

ARL computation

1. Markov chain approximation (Brook/Evans, 1972, CUSUM) Lucas/Saccucci (1990),
2. Nyström method (Vance, 1986, CUSUM)

Crowder (1987),

## ADVANCED MASK

## TECHNOLOGY CENTER

ARL computation

1. Markov chain approximation (Brook/Evans, 1972, CUSUM) Lucas/Saccucci (1990),
2. Nyström method (Vance, 1986, CUSUM) Crowder (1987),
3. Champ/Rigdon (1991): comparison of the previous ones,

## ADVANCED MASK

## TECHNOLOGY CENTER

ARL computation

1. Markov chain approximation (Brook/Evans, 1972, CUSUM) Lucas/Saccucci (1990),
2. Nyström method (Vance, 1986, CUSUM) Crowder (1987),
3. Champ/Rigdon (1991): comparison of the previous ones,
4. Monte Carlo,
5. ...,

## ADVANCED MASK

## TECHNOLOGY CENTER

## ARL computation

1. Markov chain approximation (Brook/Evans, 1972, CUSUM) Lucas/Saccucci (1990),
2. Nyström method (Vance, 1986, CUSUM) Crowder (1987),
3. Champ/Rigdon (1991): comparison of the previous ones,
4. Monte Carlo,
5. ...,
6. Collocation (Fellner, 1990, CUSUM) Gianino/Champ/Rigdon (1990).

## ADVANCED MASK

Application to upper $S^{2}$ EWMA ARLs I
$n=5, \lambda=0.18, c=2.90922\left(\right.$ final $E_{\infty}(L)$ value is 250)


## ADVANCED MASK

Application to upper $S^{2}$ EWMA ARLs II
$n=3, \lambda=0.18, c=3.61384$ (final $E_{\infty}(L)$ value is 502.34)


## ADVANCED MASK

## TECHNOLOGY CENTER

Application to upper $S^{2}$ EWMA ARLs III

$$
n=2, \lambda=0.025, c=1.66186\left(\text { final } E_{\infty}(L) \text { value is } 250\right)
$$



## ADVANCED MASK

## TECHNOLOGY CENTER

Numerics

- $f\left(z_{i-1} \rightarrow z_{i}\right)=0$ for $z_{i}<(1-\lambda) z_{i-1} \rightsquigarrow$ Nyström fails,


## ADVANCED MASK

## TECHNOLOGY CENTER

Numerics

- $f\left(z_{i-1} \rightarrow z_{i}\right)=0$ for $z_{i}<(1-\lambda) z_{i-1} \rightsquigarrow$ Nyström fails,
- product Nyström,


## ADVANCED MASK

## TECHNOLOGY CENTER

Numerics

- $f\left(z_{i-1} \rightarrow z_{i}\right)=0$ for $z_{i}<(1-\lambda) z_{i-1} \rightsquigarrow$ Nyström fails,
- product Nyström,
- collocation: $\operatorname{ARL}(z)=\sum_{i=1}^{N} c_{i} T_{i}(z)$,
$T_{i}(z)$ - monomials, Lagrange or Chebyshev polynomials


## ADVANCED MASK

Application to upper $S^{2}$ EWMA ARLs I
$n=5, \lambda=0.18, c=2.90922\left(\right.$ final $E_{\infty}(L)$ value is 250)


## ADVANCED MASK

Application to upper $S^{2}$ EWMA ARLs II
$n=3, \lambda=0.18, c=3.61384$ (final $E_{\infty}(L)$ value is 502.34)


## ADVANCED MASK

Application to upper $S^{2}$ EWMA ARLs III

$$
n=2, \lambda=0.025, c=1.66186\left(\text { final } E_{\infty}(L) \text { value is } 250\right)
$$



## ADVANCED MASK

## TECHNOLOGY CENTER

## How fast is the collocation approach?

$$
n=2, \lambda=0.025, c=1.66186\left(\text { final } E_{\infty}(L) \text { value is } 250\right)
$$

| Method | matrix dimension $N$ |  |  |  |  |  |
| :---: | ---: | ---: | ---: | ---: | ---: | :---: |
|  | 25 | 51 | 101 | 201 | 301 |  |
| Markov chain | 103.7077 | 307.4809 | 254.6729 | 250.3782 | 249.3206 |  |
|  | $<1^{1}$ | 1 | 3 | 13 | 39 |  |
| factor Nyström | $<0$ | 376.0594 | 256.6795 | 250.4456 | 250.0908 |  |
|  | $<1$ | 1 | 2 | 9 | 27 |  |
| Collocation | 249.999 | 249.9997 | 249.9997 | 249.9997 | 249.9997 |  |
|  | 1 | 3 | 11 | 40 | 101 |  |

[^0]
## ADVANCED MASK

## TECHNOLOGY CENTER

## Modifications etc.

- two-sided or one-sided with reflection barrier: piecewise collocation,


## ADVANCED MASK

## TECHNOLOGY CENTER

## Modifications etc.

- two-sided or one-sided with reflection barrier: piecewise collocation,
- similar ideas could be employed for $\bar{X}-S^{2}$ EWMA charts enhance Gan (1995),


## ADVANCED MASK

## TECHNOLOGY CENTER

## Modifications etc.

- two-sided or one-sided with reflection barrier: piecewise collocation,
- similar ideas could be employed for $\bar{X}-S^{2}$ EWMA charts enhance Gan (1995),
- for $\ln S^{2}$ EWMA charts the Gauss-Legendre Nyström method is the most powerful - Crowder/Hamilton (1992).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Comparison $S^{2}$ and $\ln S^{2}$ EWMA charts

Setup: derived from Crowder/Hamilton (1992)

## ADVANCED MASK

## TECHNOLOGY CENTER

Comparison $S^{2}$ and $\ln S^{2}$ EWMA charts

Setup: derived from Crowder/Hamilton (1992)

1. $\ln S^{2}$ EWMA: $z_{\text {reflect }}=\ln \sigma_{0}^{2}$ or $E_{\sigma_{0}}\left(\ln S_{i}^{2}\right)$

$$
Z_{0}=z_{\text {reflect }}, Z_{i}=\max \left\{(1-\lambda) Z_{i-1}+\lambda \ln S_{i}^{2}, z_{\text {reflect }}\right\}
$$

## ADVANCED MASK

Comparison $S^{2}$ and $\ln S^{2}$ EWMA charts

Setup: derived from Crowder/Hamilton (1992)

1. $\ln S^{2}$ EWMA: $z_{\text {reflect }}=\ln \sigma_{0}^{2}$ or $E_{\sigma_{0}}\left(\ln S_{i}^{2}\right)$

$$
Z_{0}=z_{\text {reflect }}, Z_{i}=\max \left\{(1-\lambda) Z_{i-1}+\lambda \ln S_{i}^{2}, z_{\text {reflect }}\right\}
$$

2. $S^{2} \mathrm{EWMA}: z_{\text {reflect }}=\sigma_{0}^{2}=E_{\sigma_{0}}\left(S_{i}^{2}\right)$

$$
Z_{0}=z_{\text {reflect }}, Z_{i}=\max \left\{(1-\lambda) Z_{i-1}+\lambda S_{i}^{2}, z_{\text {reflect }}\right\}
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

Comparison $S^{2}$ and $\ln S^{2}$ EWMA charts

Setup: derived from Crowder/Hamilton (1992)

1. $\ln S^{2}$ EWMA: $z_{\text {reflect }}=\ln \sigma_{0}^{2}$ or $E_{\sigma_{0}}\left(\ln S_{i}^{2}\right)$

$$
Z_{0}=z_{\text {reflect }}, Z_{i}=\max \left\{(1-\lambda) Z_{i-1}+\lambda \ln S_{i}^{2}, z_{\text {reflect }}\right\}
$$

2. $S^{2}$ EWMA: $z_{\text {reflect }}=\sigma_{0}^{2}=E_{\sigma_{0}}\left(S_{i}^{2}\right)$

$$
Z_{0}=z_{\text {reflect }}, Z_{i}=\max \left\{(1-\lambda) Z_{i-1}+\lambda S_{i}^{2}, z_{\text {reflect }}\right\}
$$

3. both: $\lambda \in\{0.05,0.16,0.32\}, E_{\infty}(L)=200, \sigma_{0}^{2}=1$.

## ADVANCED MASK

## Comparison $S^{2}$ and $\ln S^{2}$ EWMA charts

Results: ARL

| $\sigma^{2}$ | $\lambda=0.05$ |  |  | $\lambda=0.16$ |  |  | $\lambda=0.32$ |  |  |
| :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: |
|  | 0 | -. 267 |  | 0 | -. 267 |  | 0 | -. 267 |  |
| 1 | 200.00 | 200.00 | 200.00 | 200.00 | 200.00 | 200.00 | 200.00 | 200.00 | 200.00 |
| $1.1{ }^{2}$ | 43.04 | 41.55 | 37.78 | 45.59 | 43.19 | 43.44 | 48.93 | 46.90 | 50.50 |
| $1.2{ }^{2}$ | 18.10 | 19.92 | 16.71 | 18.54 | 18.46 | 17.42 | 19.63 | 19.12 | 20.05 |
| $1.3{ }^{2}$ | 10.75 | 13.11 | 10.32 | 10.52 | 11.11 | 9.85 | 10.73 | 10.79 | 10.74 |
| $1.4{ }^{2}$ | 63 | 9.93 | 7.39 | 7.20 | 7.96 | 6.68 | 7.08 | 7.34 | 6.93 |
| $1.5{ }^{2}$ | 5.97 | 8.11 | 5.74 | 5.49 | 6.27 | 5.03 | 5.24 | 5.57 | 5.03 |
| $2^{2}$ | 3.17 | 4.67 | 2.74 | 2.77 | 3.37 | 2.33 | 2.44 | 2.78 | 2.18 |

## ADVANCED MASK

## TECHNOLOGY CENTER

Calculating limits: quick and dirty vs. costly and correct

$$
n=5, E_{\infty}(L)=370, \text { threshold }=\sigma_{0}^{2}+\sigma_{0}^{2} \sqrt{\frac{\lambda}{2-\lambda}} \times \begin{cases}c_{\text {coll }} \sqrt{\frac{2}{n-1}} & , \text { correct } \\ \frac{\chi_{n-1 ; 1-1 / 370}^{2}}{n-1}-1 & , \text { quick and dirty }\end{cases}
$$



## ADVANCED MASK

Running for the "optimal" $\lambda$

$$
n=5, E_{\infty}(L)=250, \sigma_{1}=1.5, \text { Mittag et al. (1998) }
$$



## ADVANCED MASK

## Very small $\lambda$

$$
n=5, E_{\infty}(L)=250, \sigma_{1}=1.5, \text { Mittag et al. (1998) }
$$



## ADVANCED MASK

## Very small $\lambda$

" winning scheme"

$$
\begin{aligned}
\lambda & =0.000042 \\
c & =0.000064375308
\end{aligned}
$$

## ADVANCED MASK

## Very small $\lambda$

" winning scheme"

$$
\begin{aligned}
\lambda & =0.000042 \\
c & =0.000064375308 \\
\widehat{E_{\infty}(L)} & =250.103 \pm 0.091 \\
\widehat{E_{1}(L)} & =1.3628 \pm 0.0000 \\
& 10^{9} \text { rep. }
\end{aligned}
$$

## ADVANCED MASK

## Very small $\lambda$

" winning scheme"

$$
\begin{aligned}
& \lambda=0.000042 \\
& c=0.000064375308 \\
& \widehat{E_{\infty}(L)}=250.103 \pm 0.091, \\
& \widehat{E_{1}(L)}=1.3628 \pm 0.0000, \\
& 10^{9} \text { rep. } \\
& P_{\infty}(L=1) \approx 0.4
\end{aligned}
$$

## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{R}^{\text {R }}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{R}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{R}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{R}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{P}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{P}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


## ADVANCED MASK

## TECHNOLOGY CENTER

## Conclusions

- EWMA control charts for the variance were often applied, but the accuracy in computing their ARL values was poor.
- Collocation allows to cure these accuracy problems.
- The algorithm will be implemented in $\mathbb{R}$ library spc.
- The quick and dirty approach of deriving $S^{2}$ EWMA control limits provides suitable results.
- Now, we are able to compute the ARL of $S^{2}$ EWMA control charts for very small $\lambda$.
- $S^{2}$ EWMA seems to be better than EWMA $\ln S^{2}$ (supported by earlier, more extensive comparison studies).


[^0]:    ${ }^{1} \mathrm{CPU}$ time in hundredth seconds on an Athlon XP 1.4 GHz

